

ABSTRACT OF THE DISCLOSURE:

A cleaning apparatus for a vacuum exhaust system capable of preventing redeposition of deposits on a downstream side of a vacuum pump is provided. A cold trap capable of causing deposits to be formed by cooling gas containing a sublimation component, at least one first vacuum pump disposed upstream of the cold trap, at least one first piping connecting the first vacuum pump to the cold trap, at least one second vacuum pump disposed downstream of the cold trap, and at least one second piping connecting the second vacuum pump to the cold trap are provided. At least a part of the first vacuum pump or the first piping is configured to be heated to higher than or equal to a sublimation temperature of the sublimation component. The cold trap is configured to be cooled to less than or equal to the sublimation temperature of the sublimation component.